Ning Cao, Staff Engineer, Nano-fabrication Lab, UCSB

<table>
<tr><th colspan="9">Mo Sputtering Film using Sputter#3 at RT</th></tr>
<tr><th>Pressure (mT)</th><th>DC Power (W)</th><th>Ar Flow-rate (sccm)</th><th>Time (s)</th><th>Height (mm)</th><th>Gun Angle</th><th>Rotation (%)</th><th>Mo Film Thickness (Å)</th><th>Sputtering Rate (Å/s)</th></tr>
<tr><td>3</td><td>200</td><td>25</td><td>1200</td><td>44</td><td>4</td><td>50(~10rpm)</td><td>2630</td><td>2.192</td></tr>
</table>

Figure 1 shows the profile of Mo Film.